

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
49959-220

SERIAL NO.

APPLICANT
Gilad ALMOGY, et al.FILING DATE
November 07, 2001

U.S. PTO
11/07/01
J1050 09/986 1127

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
GT	5,248,876	9/28/1993	Kerstens et al.			
GT	5,900,637	5/4/1999	Smith			
GT	6,248,988	9/19/2001	Krantz			

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
GT	EP0871052A1	10/14/1998	Europe				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

"Projection X-Ray Lithography Using Arrays of Zone Plates", M. Feldman, Electrical & Computer Engineering Department, pp. 136-144.
"Zone-plate-array lithography in the deep ultraviolet", Ihsan J. Djomehri et al., American Vacuum Society, 1998, pp. 3426-3429.
"Zone-Plate Array Lithography (ZPAL): A new maskless approach", D.J.D. Carter et al., Part of the SPIE Conference on Emerging Lithographic Technologies III, March 1999, pp. 324-332.
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"A proposal for maskless, zone-plate-array nanolithography", Henry I. Smith, American Vacuum Society, 1996, pp. 4318-4322.
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EXAMINER

DATE CONSIDERED

5-28-03

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

SHEET 1 OF 1

INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)				ATTY. DOCKET NO. 49959-220	SERIAL NO. 09/986,137	
				APPLICANT Gilad ALMOGY, et al.		
				FILING DATE November 07, 2001	GROUP 3662	
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
	US	6,248,988 B1	06/19/01	Krantz		
	US	6,043,932	03/28/00	Kusunose		
	US	6,133,986	10/17/00	Johnson		
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EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number -Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation
		WO 98/57151	12/17/98	PCT		Yes
		0678864 A1	11/02/95	Europe		No
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		0299432 A2	01/16/89	Europe		
		01263541	10/20/89	Japan		X Abstract
		2000066374	03/03/00	Japan		X Abstract
OTHER ART (including Author, Title, Date, Pertinent Pages, ETC.)						
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				
		Partial International Search Report dated 5/5/03.				
EXAMINER			DATE CONSIDERED			

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1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

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		WO 02/23172 A2	03/21/02	PCT
		EP 0948027 A2	10/06/99	Europe
		WO 01/09920 A1	02/06/01	PCT
		WO 02/15223 A1	02/21/02	PCT
		WO 02/23580 A1	03/21/02	PCT
OTHER ART (including Author, Title, Date, Pertinent Pages, Etc.)				
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.		
		International Search Report dated August 4, 2003.		
		'High throughput electron lithography with the multiple aperture pixel by pixel enhancement of resolution concept', Krull, P., J. Vac. Sci. Technol. B 16(6), Nov/Dec 1998.		
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		'A Microlens Direct-Write Concept for Lithography', Davidson, M., SPIE 3048, p. 346-355.		
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		'UV Thermoresists: Sub 100nm Imaging Without Proximity Effects', Gelbart, D. et al., SPIE Vol. 3676, pp. 786-793		
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